

133 a liquid recycling system in fluid communication with the non-thermal plasma reactor.

REMARKS

Claims 57 and 70 have been amended for purposes of clarification. Support for the amendment to claim 57 is found in the specification at page 15, lines 1-6 and page 18, lines 3-5. Support for the amendment to claim 70 is found in the specification at page 24, line 8 – page 25, line 22 and FIG. 5. Claims 88-95 have been added. Support for claim 88, 91 and 92 is found throughout the specification, particularly at page 7, lines 26-27. Support for claim 89 is found in the specification at page 7, lines 20-23 and page 10, lines 22-23. Support for claim 90 is found in the specification at page 10, lines 22-23. Support for claim 93 and 94 is found throughout the specification, particularly at page 15, line 18 – page 19, line 14 and FIG. 1. Support for claim 95 is found in the specification at page 24, line 8 – page 25, line 22 and FIG. 5. Entry of these amendments is respectfully requested.

Respectfully submitted,

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**Marked-up Version of Amended Claims
Pursuant to 37 C.F.R. §§ 1.121(b)-(c)**

The claims have been amended as follows:

57. (Amended) A process for treating a halogen-containing gas, comprising:
providing a chamber defining at least one gas inlet for receiving a feed gas mixture that includes a halogen-containing gas and a gaseous reducing agent, and at least one water inlet for receiving liquid water;

providing at least one first electrode disposed within the chamber;

providing at least one second electrode disposed within the chamber;

flowing the liquid water over at least a portion of the first electrode; and

applying electric potential to at least one of the first [and] or second electrodes so as to generate a plasma in the feed gas mixture and reduce the halogen-containing gas.

70. (Amended) A system for treating fluorine gas, comprising:

a non-thermal plasma reactor for converting fluorine gas to hydrogen fluoride;

a fluorine gas source in fluid communication with the non-thermal plasma reactor;

[a hydrogen gas source in fluid communication with the non-thermal plasma reactor;] and

a liquid water source in fluid communication with the non-thermal plasma reactor.